Appl. No. 10/723,456 Amdt. dated October 1, 2004 Reply to Office Action of July 1, 2004

## AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

Claims 1-47 (cancelled)

1 48. (new) An integrated semiconductor structure comprising: 2 a multijunction solar cell including a first photoactive junction formed in a 3 substrate forming a first subcell, and a second photoactive junction formed in a region 4 overlying said substrate forming a second subcell; and 5 means integral to a portion of said first subcell for passing current when said 6 multijunction solar cell is shaded. 1 49. (new) The structure as defined in claim 48, wherein said means for passing current is 2 a bypass diode formed on the substrate. 1 50. (new) The structure as defined in claim 49, wherein said first subcell and said bypass 2 diode are formed in the same process. 1 51. (new) The structure as defined in claim 49, wherein the bypass diode has a Schottky 2 junction. 1 An integrated semiconductor structure comprising: 52. (new) 2 a multijunction solar cell including a bottom subcell formed on a substrate; and 3 means integral to a portion of said bottom subcell for passing current when said multijunction solar cell is shaded. 4 1 The structure as defined in claim 52, wherein said bottom subcell is formed on 53. (new) 2 a first portion of the substrate and said means for passing current is a bypass diode formed on

a second portion of the substrate that is laterally spaced from said first portion.

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- 1 54. (new) The structure as defined in claim 52, wherein said first subcell and said bypass
- 2 diode are formed in the same process.
- 1 55. (new) The structure as defined in claim 52, wherein said epitaxially grown diode is
- 2 electrically connected across the subcells of the multijunction solar cell to protect said
- 3 subcells against reverse biasing.
- 1 56. (new) The structure as defined in claim 52, wherein the bypass diode has a Schottky
- 2 junction.
- 1 57. (new) An integrated semiconductor structure comprising:
- a multijunction solar cell including a first solar cell formed on a substrate; and
- a bypass diode integral to a portion of said first solar cell and electrically
- 4 connected to the base of said cell for passing current when said multijunction solar cell is
- 5 shaded.
- 1 58. (new) The structure as defined in claim 56, wherein said first solar cell is formed on a
- 2 first portion of the substrate and said bypass diode is formed on a second portion of the
- 3 substrate spaced apart from said first portion.
- 1 59. (new) The structure as defined in claim 56, further comprising a metal layer
- 2 connecting said bypass diode to the base of the first solar cell.
- 1 60. (new) An integrated semiconductor structure comprising:
- a multijunction solar cell including first and second solar cells on a substrate;
- means integral to a portion of said first solar cell for passing current when said
- 4 multijunction solar cell is shaded; and

- 5 a metal layer connecting said multijunction solar cell and said means for
- 6 passing current, wherein one end of said metal layer is coupled to the base of said first solar
- 7 cell and another end of said metal layer is coupled to one terminal of said means for passing
- 8 current.
- 1 61. (new) The structure as structure as defined in claim 59, wherein said first solar cell is
- 2 formed on a first portion of the substrate, and said means for passing current is a bypass diode
- 3 formed on a second portion of the substrate.
- 1 62. (new) The structure as defined in claim 60, wherein said first portion and said second
- 2 portion are separated by a trough, and said metal layer lies over said trough.
- 1 63. (new) The structure as defined in claim 59, wherein both said first solar cell grown
- 2 and said bypass diode are formed in the same process.
- 1 64. (new) The structure as defined in claim 62, wherein said epitaxially grown diode is
- 2 electrically connected across at least said first and second cells to protect said first and second
- 3 cells against reverse biasing.
- 1 65. (new) A solar cell semiconductor device comprising:
- an integral semiconductor body having a sequence of layers of
- 3 semiconductor material including a first region in which the sequence of layers of
- 4 semiconductor material forms the first cell of a multijunction solar cell; and
- 5 a second region laterally spaced apart from said first region and in which the
- 6 sequence of layers corresponding to the sequence of layers forming said first cell forms a
- 7 bypass diode to protect said multijunction solar cell against reverse biasing.

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- 1 66. (new) A device as defined in claim 65, wherein the sequence of layers of said first
- 2 cell and the sequence of layers of the bypass diode are formed in the same process step.
- 1 67. (new) A device as defined in claim 65, wherein the semiconductor body includes a
- 2 Ge substrate, and at least one of the cells is fabricated at least in part with GaAs.
- 1 68. (new) A solar cell semiconductor device comprising:
- 2 a substrate;
- a sequence of layers of material deposited on said substrate, including a first
- 4 region in which the sequence of layers of material forms at least one cell of a multijunction
- 5 solar cell, and a second region in which the corresponding sequence of layers forms a bypass
- 6 diode to protect said cell against reverse biasing; and
- 7 a discontinuous lateral conduction layer deposited on said substrate for making
- 8 electrical contact to an active region of said bypass diode.
- 1 69. (new) A device as defined in claim 68, wherein said lateral conduction layer in the
- 2 first region is physically separated from the lateral conduction layer in the second region.
- 1 70. (new) A device as defined in claim 68, wherein said lateral conduction layer is a
- 2 highly doped layer.
- 1 71. (new) A device as defined in claim 70, wherein said lateral conduction layer is
- 2 composed of GaAs.
- 1 72. (new) A device as defined in claim 68, wherein one of the layers of said sequence of
- 2 layers is an etch stop layer, and said lateral conduction is disposed directly over said etch stop
- 3 layer.

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- 1 73. (new) A device as defined in claim 68, wherein said substrate includes a photoactive
- 2 junction.
- 1 74. (new) A device as defined in claim 73, wherein said substrate is germanium.
- 1 75. (new) A device as defined in claim 73, wherein said substrate forms an electrical
- 2 connection path between said multijunction solar cell as said bypass diode.
- 1 76. (new) A device as defined in claim 68, further comprising:
- a metal layer deposited on a portion of said substrate and over at least a portion of said
- 3 second region and functioning to (i) electrically short layers of said second region, and (ii)
- 4 connect the substrate to said lateral conduction layer to complete the electrical circuit between
- 5 the multijunction solar cell and the bypass diode.
- 1 77. (new) A solar cell semiconductor device comprising:
- 2 a substrate;
- a sequence of layers of semiconductor material deposited on said substrate
- 4 including a first region in which the sequence of layers of semiconductor material forms at
- 5 lease one cell of a multijunction solar cell, and a second region in which the corresponding
- 6 sequence of layers forms a bypass diode to protect said cell against reverse biasing; and
- 7 a lateral conduction layer deposited on said substrate including a first portion disposed
- 8 in said first region, and a second portion disposed in said second region and physically
- 9 separated from said first portion.
- 1 78. (new) A device as defined in claim 77, wherein said lateral conduction layer is a
- 2 highly doped layer.

- 1 79. (new) A device as defined in claim 77, wherein said lateral conduction layer is
- 2 composed of GaAs.
- 1 80. (new) A device as defined in claim 77, wherein one of the layers of said sequence of
- 2 layers is an etch stop layer, and said lateral conduction layer is disposed directly over said
- 3 etch stop layer.
- 1 81. (new) A device as defined in claim 77, wherein said second portion of said lateral
- 2 conduction layer makes electrical contact with a first InGaP layer of said bypass diode.
- 1 82. (new) A device as defined in claim 81, wherein said bypass diode further comprises a
- 2 GaAs layer disposed over said first InGaP layer, and a second InGaP layer disposed over said
- 3 GaAs layer.
- 1 83. (new) A device as defined in claim 82, further comprising a metal layer deposited
- 2 over said second InGaP layer and forming a Schottky junction with said second InGaP layer.
- 1 84. (new) A device as defined in claim 77, wherein said substrate includes a photoactive
- 2 junction.
- 1 85. (new) A device as defined in claim 77 wherein said substrate is germanium.
- 1 86. (new) A device as defined in claim 77, wherein said substrate forms an electrical
- 2 connection path between said multijunction solar cell as said bypass diode.
- 1 87. (new) A device as defined in claim 86, further comprising a metal layer deposited on
- 2 a portion of said substrate and over at least a portion of said second region and functioning to
- 3 connect the substrate to a portion of said lateral conduction layer for completing the electrical
- 4 circuit between the multijunction solar cell and the bypass diode.

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- 1 88. (new) A solar cell semiconductor device comprising:
- 2 a substrate;
- a sequence of layers of semiconductor material deposited on said substrate, including a
- 4 first region in which the sequence of layers of semiconductor material forms
- 5 at least one cell of a multijunction solar cell; and a second region in which the corresponding
- 6 sequence of layers forms a bypass diode to protect said cell against reverse biasing; and
- 7 a highly conductive lateral conduction layer deposited on said substrate for making
- 8 electrical contact with one layer of said bypass diode and forming a contact region to allow
- 9 said bypass diode to be electrically connected to said multijunction solar cell.
- 1 89. (new) A device as defined in claim 88, further comprising a metal layer deposited on
- 2 a portion of said substrate and over at least a portion of said second region and functioning to
- 3 connect the substrate to a portion of said lateral conduction layer for completing the electrical
- 4 circuit between the multijunction solar cell and the bypass diode.
- 1 90. (new) A device as defined in claim 88, wherein said lateral conduction layer includes
- 2 a first portion disposed in said first region, and a second portion disposed in said second
- 3 region and separated from the first portion.
- 1 91. (new) A device as defined in claim 88, wherein said lateral conduction layer is a
- 2 highly doped layer composed of GaAs.
- 1 92. (new) A device as defined in claim 90, wherein said second portion of said lateral
- 2 conduction layer makes electrical contact with a first active layer of said bypass diode.
- 1 93. (new) A solar cell semiconductor device comprising:
- 2 a substrate;

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- a sequence of layers of semiconductor material deposited on said substrate, including a
- 4 first region in which the sequence of layers of semiconductor material forms at least one cell
- of a multijunction solar cell; and a second region laterally spaced apart from said first region;
- 6 and
- a metal layer deposited on a portion of said substrate and over at least a portion of said
- 8 second region for electrically shorting the layers of said second region to enable a bypass
- 9 diode to be formed in said second region.
- 1 94. (new) A device as defined in claim 93,
- wherein said metal layer connects said multijunction solar cell and said bypass diode
- 3 with one end of said metal layer being coupled to the base of said one solar cell and another
- 4 end of said metal layer is coupled to one terminal of said bypass diode.
- 1 95. (new) A device as defined in claim 93, wherein said first portion and said second
- 2 portion are separated by a trough, and said metal layer lies over at least a portion of said
- 3 trough.
- 1 96. (new) A device as defined in claim 93, wherein at least one layer of said first solar
- 2 cell and said bypass diode are substantially simultaneously formed in the same process.
- 1 97. (new) A device as defined in claim 93, wherein said bypass diode is electrically
- 2 connected by said metal layer across said solar cell to protect said solar cell against reverse
- 3 biasing.
- 1 98. (new) A device as defined in claim 93 further comprising:
- a lateral conduction layer deposited on said substrate for electrically
- 3 connecting the multijunction solar cell to said bypass diode.

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